Hiden Reference: AP0002
Hiden Product: HPR-30 Vacuum Process Gas Analyser

Surface characteristics of parylene-C films in an inductively coupled O_2/CF_4 gas plasma

We investigated the degradation mechanism of OTFT performance in the plasma processing. In order to examine the origin of the degradation mechanism due to the plasma exposure, the relationships between operating parameters and plasma species should be analyzed for fabrication of high performance transistor in the plasma processing. So, we extracted the plasma species using quadrupole mass-spectrometry (QMS). Then, we applied this result for analyzing a degradation mechanism of OTFT devices.

Fig. 2 Discussing the extracted data with a co-worker
Left: Dr Yong-Hyun Ham
Right: Professor Kwang-Ho Kwon

Fig. 1 Photograph of the Hiden Mass Spectrometer in use in our lab

Project Summary by:
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Hiden Product:
HPR-30 Vacuum Process Gas Analyser
Follow the link to the product catalogue on our website for further information:
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